

| | Hits | Search Text | DBs |
|----|------|---|---|
| 40 | 1 | ((photoresist or resist) same (non\$4chemical\$5amplif\$6) same (resin\$3) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3)) and (photo\$5active or photoactivat\$4 or (light near9 activat\$4)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 41 | 1 | ((photoresist or resist) same (non\$4chemical\$5amplif\$6) same (resin\$3) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 42 | 15 | ((photoresist or resist) same (resin\$3) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3)) and (photo\$5active or photoactivat\$4 or (light near9 activat\$4)) and (non\$4 near9 chemical\$2 near9 amplif\$6) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 43 | 34 | ((photoresist or resist) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3)) and ((photo\$5active or photoactivat\$4 or (light near9 activat\$4)) same acid) and (non\$4 near9 chemical\$2 near9 amplif\$6) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |